

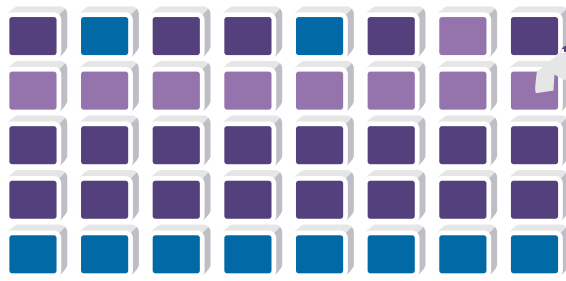
Proteus LRC

Full-Chip Verification Through Process Window

Overview

Proteus LRC (lithography rule check) is Synopsys' post-optical proximity correction (OPC) verification tool enabling fast and accurate hotspot detection across the process window for full-chip mask validation within the highly-scalable Proteus Pipeline Technology. Problem areas are quickly identified, enabling more robust design and OPC practices early in the development cycle while reducing the risk of device failure later during the production flow. Improve time to market for

new designs of 45nm and 32nm nodes (1.2-0.8µm) for IBM (em) (sc)-4e) TEE/Span Kang (en-1100 B (33)-2d)-et fciin@m[]-8(





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